

Photopolymerization of Acrylic Acid Derivatives in the Presence of (4-Methoxyphenyl)methylsilane

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The bulk thermal and photopolymerization of acrylic acid derivatives (MMA, MA) with (4-methoxyphenyl)methylsilane were performed to produce poly(MMA)s and poly(MA)s containing (4-methoxyphenyl)methylsilyl moiety presumably as an end group. It was found for both thermal and photopolymerization that while the polymerization yields and polymer molecular weight decreased as the relative silane concentration increases, the TGA residue yields and the relative intensities of SiH IR stretching bands increased with increasing molar ratio of silane over MMA and MA.